


8-11, 15, and 18-21 is attached for the Examiner's convenience pursuant to new rule 37 C.F.R. 1.121 (c)(1)(ii). No new matter has been introduced by these amendments.

The examiner is respectfully requested to consider the above preliminary amendment prior to examination of the application.

If there are any fee due in connection with the filing of this Preliminary Amendment, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,  
GARRETT & DUNNER, L.L.P.

By:   
David W. Hill  
Reg. No. 28,220

Date: April 6, 2001  
DWH/FPD/sci



Attorney Docket No.:08038.0044  
Customer Number: 22,852

**Appendix Detailing Amendments to the Specification**  
**PURSUANT TO 37 C.F.R. § 1.21(c)(1)(ii)**

**CLAIM AMENDMENTS:**

Applicants submit the following claims with strikeouts and underlining for the Examiner's convenience as required by new rule 37 C.F.R. 1.121 (c)(1)(ii).

This paper is not intended to be entered.

**IN THE CLAIMS:**

4. (Amended) The electrode according to claim 2 [any one of claims 1 to 3], wherein a shower head portion that supplies a gas is provided on a lower surface of the base metal.

5. (Amended) The electrode according to claim 2 [any one of claims 1 to 4], wherein the electrode is configured so that a high frequency voltage is applied thereto.

8. (Amended) The susceptor according to claim 6 [or 7], wherein the upper ceramic-metal composite and the electrostatic chuck are brazed together.

9. (Amended) The susceptor according to claim 6 [or 7], wherein the upper ceramic-metal composite and the electrostatic chuck are forge-welded together.

10. (Amended) The susceptor according to claim 6 [or 7], wherein the upper ceramic-metal composite and the electrostatic chuck are adhered together.

11. (Amended) The susceptor according to claim 6 [claims 6 to 10], wherein the susceptor is configured so that a high frequency voltage is applied thereto.

15. (Amended) The plasma processing apparatus according to claim 12 [any one of claims 12 to 14], wherein a shower head portion for supplying a gas is provided on a lower surface of the base metal.

18. (Amended) The plasma processing apparatus according to claim 16 [any one of claims 16 or 17], wherein the susceptor is provided with heat transfer gas passages that supplies a heat transfer gas to a surface of the electrostatic, the passage passing through the susceptor.

19. (Amended) The plasma processing apparatus according to claim 16 [any one of claims 16 to 18], wherein the upper ceramic-metal composite and the electrostatic chuck are brazed together.

20. (Amended) The plasma processing apparatus according to claim 16 [any one of claims 16 to 18], wherein the upper ceramic-metal composite and the electrostatic chuck are forge-welded together.

21. (Amended) The plasma processing apparatus according to claim 16 [any one of claims 16 to 18], wherein the upper ceramic-metal composite and the electrostatic chuck are adhered together.